OIPE JC35 FEB 2 2 2005 TRADEMARK OFFICE



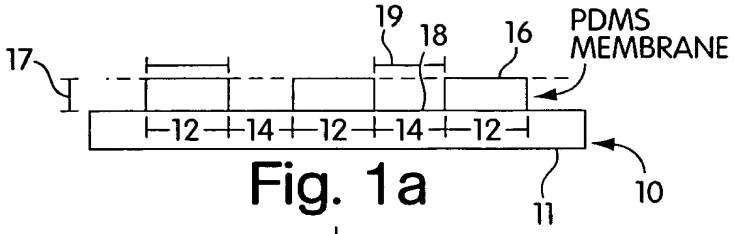



Fig. 1a

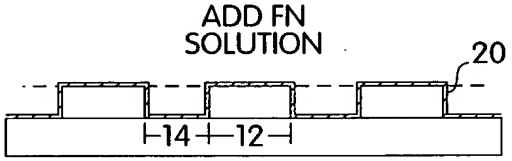



Fig. 1b

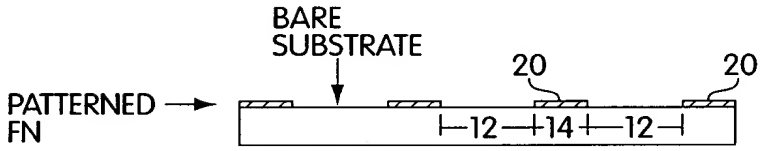



Fig. 1c

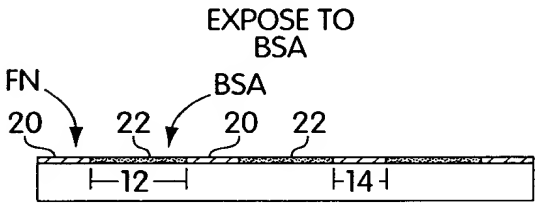



Fig. 1d

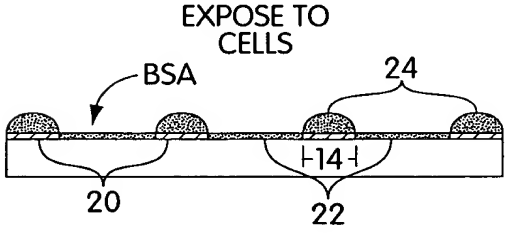



Fig. 1e

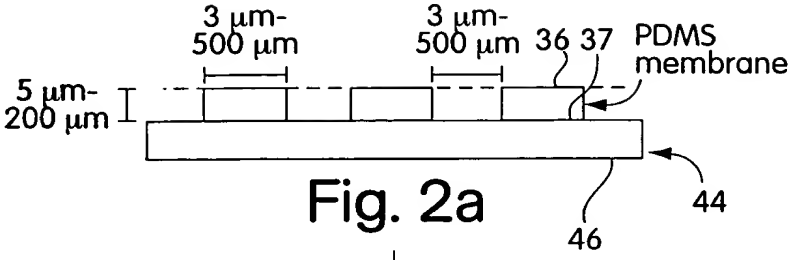



Fig. 2a

ADD BSA
SOLUTION

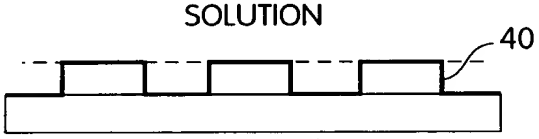



Fig. 2b

1. RINSE WITH PBS
2. PEEL MEMBRANE AND
TRANSFER TO CLEAN SUBSTRATE

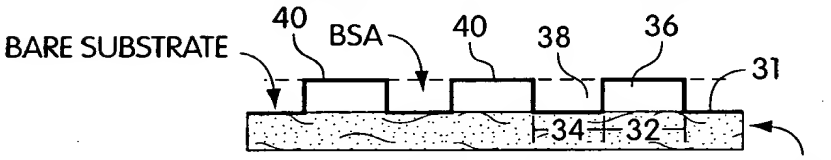



Fig. 2c

INCUBATE WITH FN

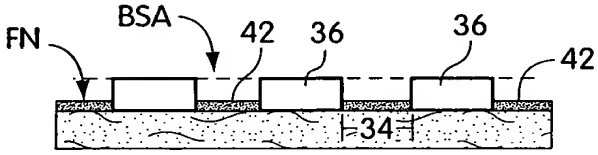



Fig. 2d

EXPOSE TO 1ST
CELL TYPE

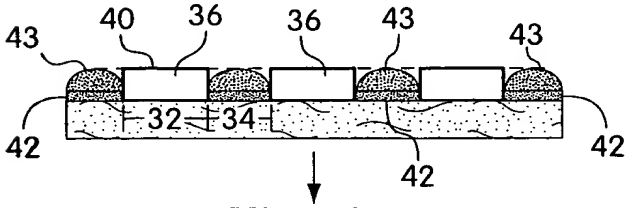



Fig. 2e

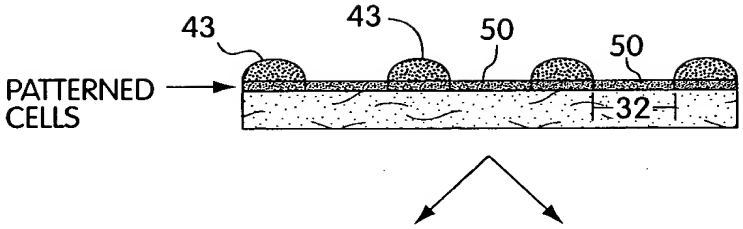



Fig. 2f

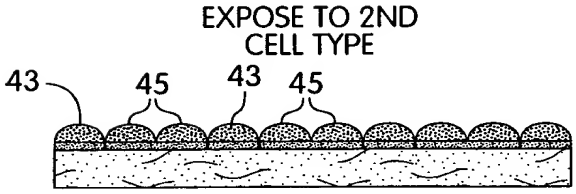



Fig. 2g

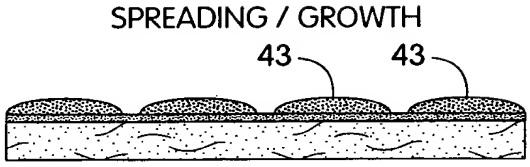



Fig. 2h

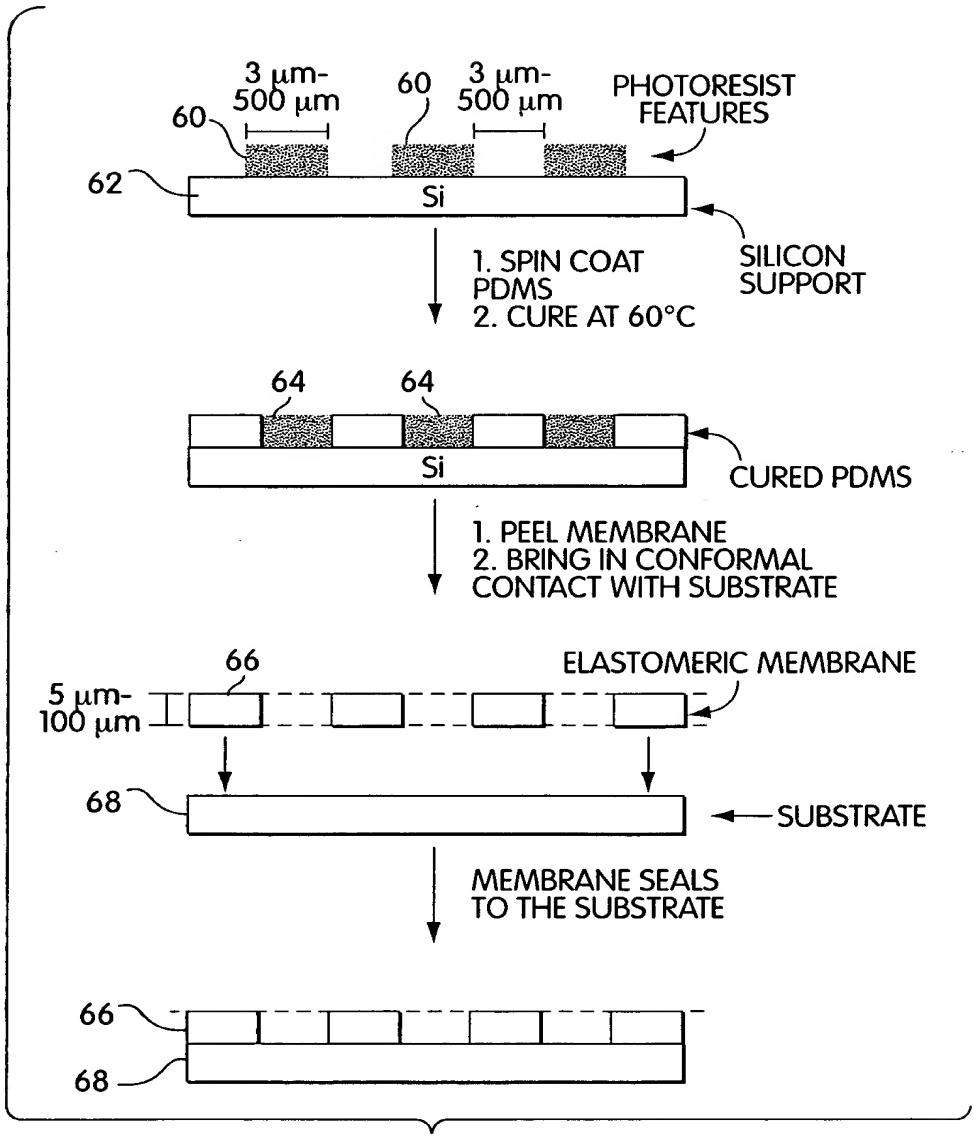

3 μm-
500 μm
60
60
3 μm-
500 μm
PHOTORESIST
FEATURES
62
Si
SILICON
SUPPORT
1. SPIN COAT
PDMS
2. CURE AT 60°C
64
64
Si
CURED PDMS
1. PEEL MEMBRANE
2. BRING IN CONFORMAL
CONTACT WITH SUBSTRATE
66
ELASTOMERIC MEMBRANE
5 μm-
100 μm
68
SUBSTRATE
MEMBRANE SEALS
TO THE SUBSTRATE
66
68

Fig. 3

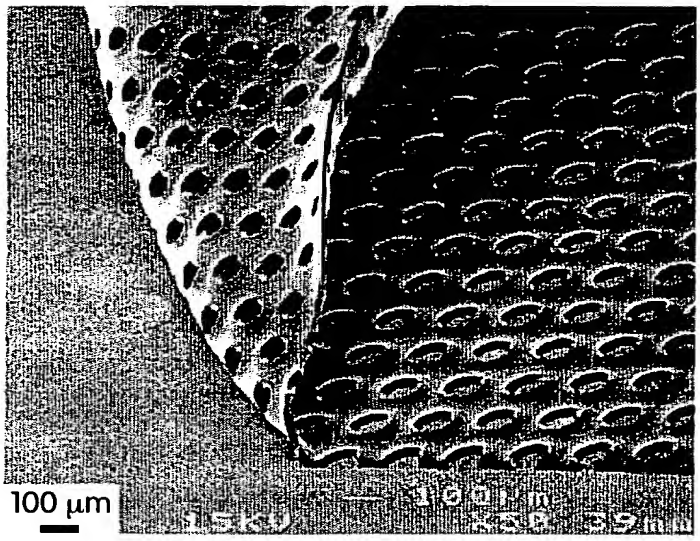



Fig. 4

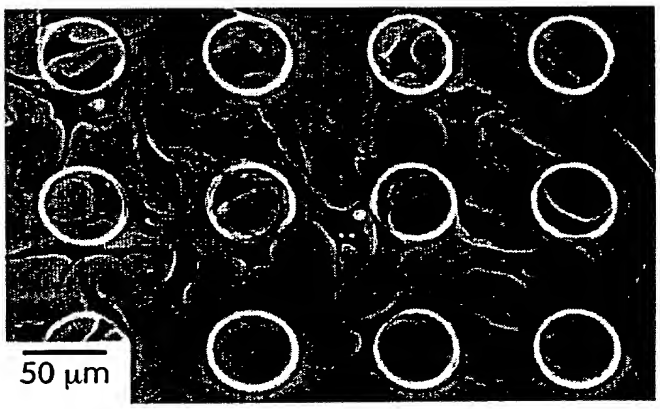



Fig. 5a

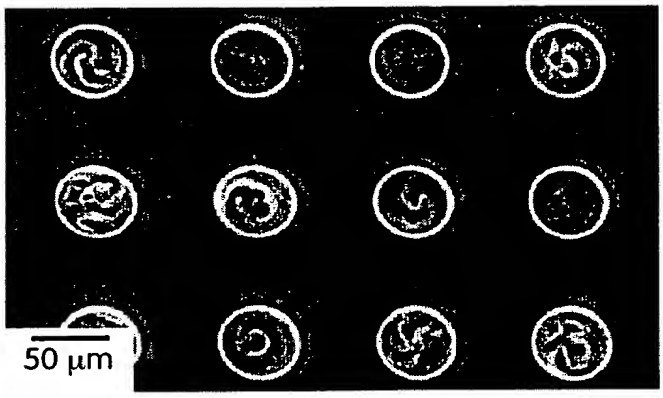



Fig. 5b

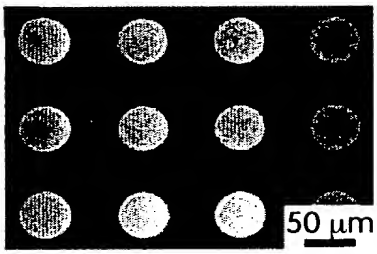



Fig. 6a

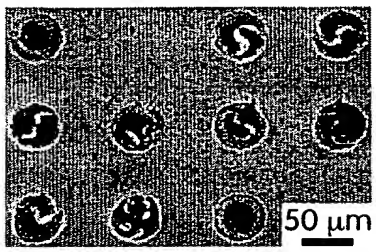



Fig. 6b

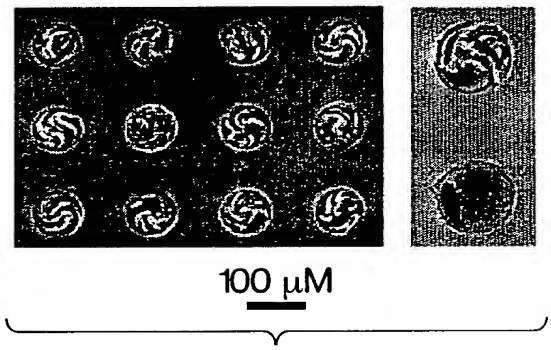



Fig. 7a

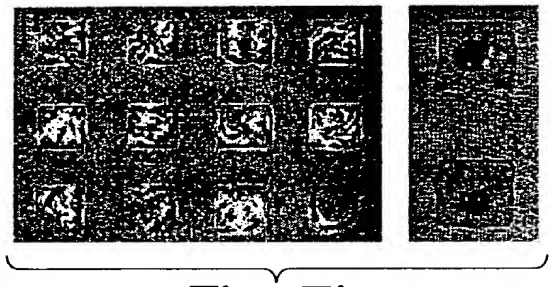
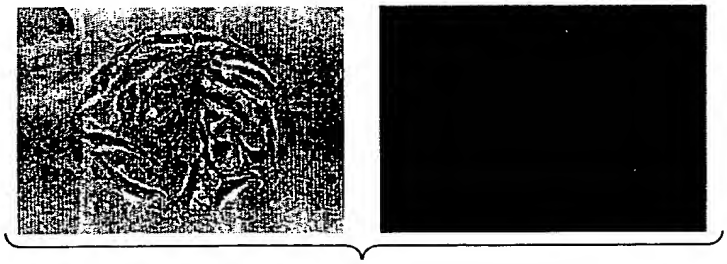


Fig. 7b



250 μM, A-B

Fig. 8a

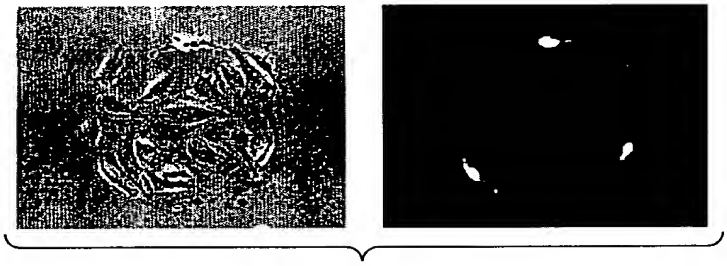
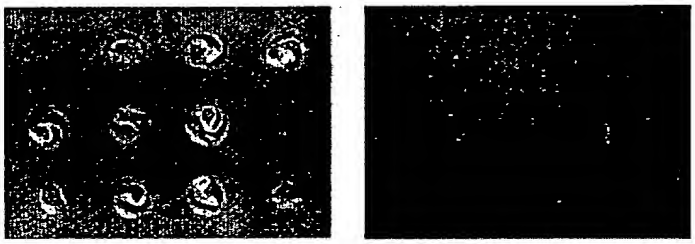


Fig. 8b



100 μM, C-D

Fig. 8c

300 μM, E

Fig. 8d

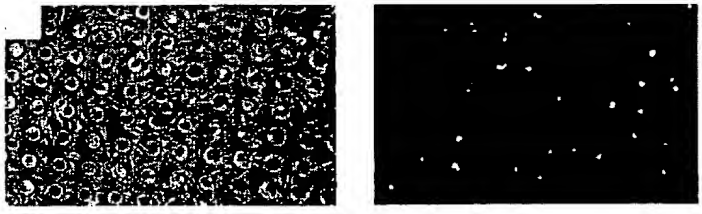


Fig. 8e

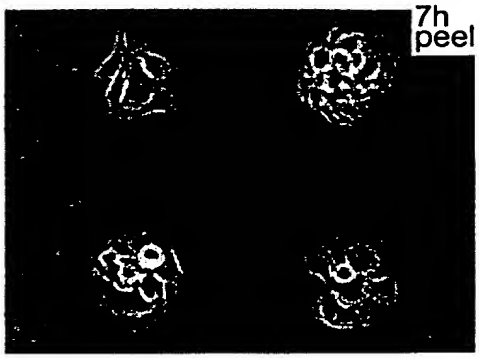



Fig. 9a

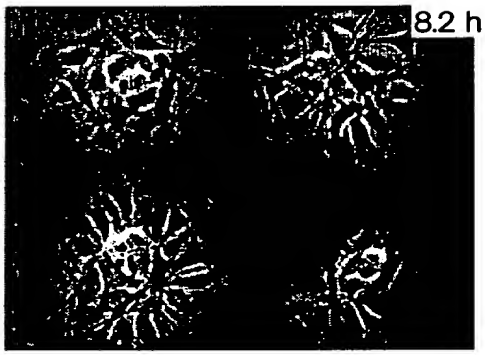



Fig. 9b

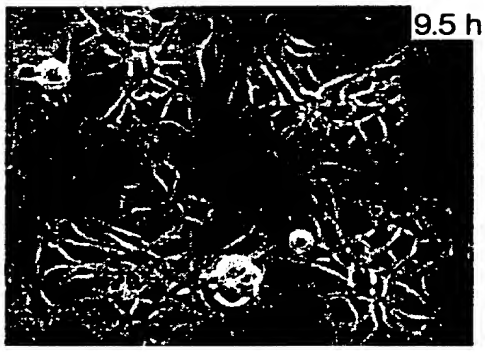



Fig. 9c

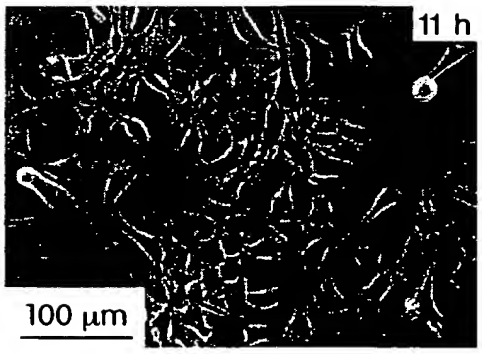



Fig. 9d